

Exhibit A

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tsmc 台湾积体电路

TSMC INVENTION DISCLOSURE

- **TITLE OF INVENTION - (ENGLISH ONLY)**
ENGLISH - PR MIST AUTO DETECTION SYSTEM
 - **BACKGROUND INFORMATION - CURRENT PRACTICE AND DISADVANTAGES (ENGLISH ONLY)**
 - 1) Current coated cup design and mist generation mechanism
 - a. Wafer is rotating when PR & Solvent dispensing.
 - b. PR can coated by wafer spinning.
 - c. Edge PR can remove by solvent dispense.
 - d. This solved PR dust should be exhausted by exhausted Air.
 - e. Splashed back dust become particle or defects because of solvent compound
 - 2) What's the problems?
 - a. Exhaust line choke up when PR dust piles up => Not enough Exhaust.
 - b. Machine can't check whether splashed back problem happen or not.
 - c. Splashed back makes process trouble and it makes CP Yield down.
 1. If you find out this trouble at A/M inspection this lot should be reworked.

MAIN POINTS OF CLAIM (PLEASE LIST ITEMS BY ITEM) 列出理赔要点(按项目列明的) (ENGLISH)

1w

- ONLY!**

 - 1) Use Laser beam to detect scattered PR dust.
 - 2) Changeable laser generator & detector height.
 - 3) Changeable laser set number.(The more the better)
 - 4) When this detector PR dust system can stop automatically.
 - 5) Attach this system on PR cup.
 - 6) Prevent PR dust P/D by this laser detector.

STATEMENT RELATING TO THE INVENTION (PLEASE LETTER BY LETTER)
PROBLEMS SOLVED OR IMPROVEMENTS OBTAINED BY THIS INVENTION (PLEASE LETTER BY LETTER ENGLISH ONLY)

- ### 1) Improve Photo Rework rate.

2) Improve CP Yield by reduction of PR dust P/D and EBR splashed back.

KEYWORD SEARCH FOR PATENT LITERATURE (ENGLISH ONLY)

Splashed back-PR mist floating particle

PATENT LITERATURE SEARCH RESULT (PLEASE NOTE THE SIMILAR PATENT NO. AND

LITERATURE CITATION IN ENGLISH ON PAGE

Can't find out(Need to Check again)

RECALLERS: REPLY TO OFTEN TESTIMONY ONLY

You can see Attachment file